Special Issue

Model Learning Predictive Control for Industrial Processes

Message from the Guest Editors

In this Special Issue, we cordially invite your contributions that will feature the latest developments in model-predictive control with regard to bringing a high level of autonomy in the technology but also controlling approaches that combine learning methods using data. Contributions that show applications on pilot plants or actual chemical processes are particularly welcome.

Guest Editors

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Deadline for manuscript submissions

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You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

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